CLAIMS

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1. A process for fabrication a metal-insulator-metal (MIM) device for actively addressing electro-optical effects comprising:

creating one or more surface relief levels in a dielectric layer over a conductive carrier wherein the surface relief levels form trenches;

depositing a first metal in the trenches;

anodizing the first metal to create a non-linear dielectric;

depositing a second metal in the trenches to create an electrical contact with the non-linear dielectric;

forming a contact with the second metal for an electro-optic effect; and transferring the MIM device to a final substrate by adhesive transfer.

- 2. The process of claim 1 wherein the creating is formed using an embossing process.
 - 3. The process of claim 1 wherein the trenches are of varying depths.
- 20 4. The process of claim 1 wherein depositing the first metal is performed by vacuum deposition.
 - 5. The process of claim 1 wherein the depositing the first metal is performed by electro-deposition.

6. The process of claim 1 wherein the depositing the second metal is performed by electro-deposition.

7. The process of claim 1 wherein the contact is a liquid crystal cell 30 contact.

- 8. The process of claim 1 wherein a single MIM is fabricated.
- 9. The process of claim 1 wherein a dual MIM is fabricated.
- 5 10. The process of claim 1 further comprising applying a transparent conductor.
 - 11. The process of claim 10 wherein the transparent conductor is PEDOT.

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- 12. The process of claim 1 wherein the first and second metals comprise alloys.
- 13. An electro-optical display that comprises MIM devices fabricated from the process of claim 1.
 - 14. A non-linear active device used to address an electro-optic effect comprising:

a non-linear capacitive element comprised of an anodized dielectric;

an addressing line formed by a first metal that contacts to the non-linear capacitive component; and

an electro-optic effect contact formed by a second metal that contacts to the non-linear capacitive component.

- 25 15. The non-linear active device of claim 14 wherein the electrooptic effect is applied to a liquid crystal cell.
 - 16. The non-linear active device of claim 14 comprises a single metal-insulator-metal (MIM) device.

- 17. The non-linear active device of claim 14 comprises a dual metal-insulator-metal (MIM) device.
- 18. The non-linear active device of claim 14 wherein the anodized 5 dielectric is Ta_2O_5 .
 - 19. The non-linear active device of claim 14 wherein the first and second metals are tantalum, niobium, titanium, copper, aluminum, or silver.
- 10 20. The non-linear active device of claim 14, wherein the first and second metals comprise alloys.
 - 21. A transparent substrate comprising the non-linear active device of claim 13.
 - 22. A liquid crystal display comprising the non-linear active device of claim 1.

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- 23. The liquid crystal display of claim 22 wherein the electro-optic effects are to liquid crystal cells.
 - 24. A process of creating a display device comprising:

fabricating an array of active addressing devices comprised of nonlinear capacitive components formed by embossing of a relief surface creating a dielectric over conductive carrier;

depositing metals using the conductive carrier as a conductive terminal;

removing the conductive carrier by transferring the array of active addressing devices onto a substrate; and

forming contacts to electro-optic components from the array of active addressing devices.

- 25. The process of claim 24 wherein the active addressing components are metal-insulator-metal (MIM) devices.
- 5 26. The process of claim 25 wherein the MIM devices are single MIM devices.
 - 27. The process of claim 25 wherein the MIM devices are dual MIM devices.
- 28. The process of claim 24 wherein the electro-optic components are liquid crystal cells.